	eiji Ishibashi	IITTAL LETTER	(Large Entity)		Docket No. NPO0005
Serial No. 009/633,002		iling Date gust 4, 2000	Examiner W. Markham		Group Art Unit
FEB 0 4	ૡૢ	APPARATUS AND A	METHOD FOR REMO	OVING A DEF	OSITED FILM
	vith is an amendmen	nt in the above-identific		ENTS:	
The fee has been	calculated and is tra	insmitted as shown be		·	
		CLAIMS AS	AMENDED		
	CLAIMS REMAINING AFTER AMENDMENT	HIGHEST # PREV. PAID FOR	NUMBER EXTRA  CLAIMS PRESENT	RATE	ADDITIONAL FEE
TOTAL CLAIMS	6 -	20 =	0	<u> </u>	<del></del>
IDEP. CLAIMS	1 -	3 =	0	x \$84.00	\$0.00
lultiple Depender	nt Claims (check if a	pplicable) ,□			\$0.00
	arge Deposit Accou e copy of this sheet		in the amount of		
A check in The Communic A duplicat	the amount of missioner is hereby a sation or credit any control sheet additional filing fees	to cover the f authorized to charge p verpayment to Depos	F.R. 1.16.		RECEN FEB 1 1 200 TC 170



PATENT NPO0005

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of (Customer No. 00832)

Keiji Ishibashi (Customer No. 00832)

Serial No. 09/633,002 (Customer No. 00832)

Filed: August 4, 2000 (Customer No. 00832)

Title: A HOT ELEMENT CVD APPARATUS (Customer No. 00832)

Examiner: W. Markham

AND A METHOD FOR REMOVING A DEPOSITED FILM

**AMENDMENT** 

Assistant Commissioner for Patents Washington, D.C. 20231

Sir:

Responsive to the Office Action dated July 5, 2001, which had a period for response which expired on October 5, 2001, which period has been extended by the enclosed Petition For Extension Of Time to expire on November 5, 2001, Applicant hereby submits the following response:

IN THE CLAIMS:

Cancel claims 17-20.

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## **REMARKS**

Claims 11-16 are at issue. Claims 17-20 have been canceled as drawn to a non-elected invention. No claims have been allowed.

Applicant reserves the right to file a divisional patent application on canceled claims 17-20.

Claims 11, 12, 15, and 16 have been rejected under 35 U.S.C. 103(a) as unpatentable over Matsuyama in view of Niino et al.

Matsuyama teaches a CVD method comprising feeding a filament of platinum, tungsten, or the like, supplying a material gas to a chamber, contacting the material gas with the heated filament to cause decomposition and/or activation of the material gas by the filament, and forming a deposition film on a substrate. Matsuyama does not teach a method